

Lecture 22 - The Si surface and the Metal-Oxide-Semiconductor Structure (*cont.*)

April 2, 2007

Contents:

1. Ideal MOS structure under bias (*cont.*)

Reading assignment:

del Alamo, Ch. 8, §8.3 (8.3.2-8.3.4)

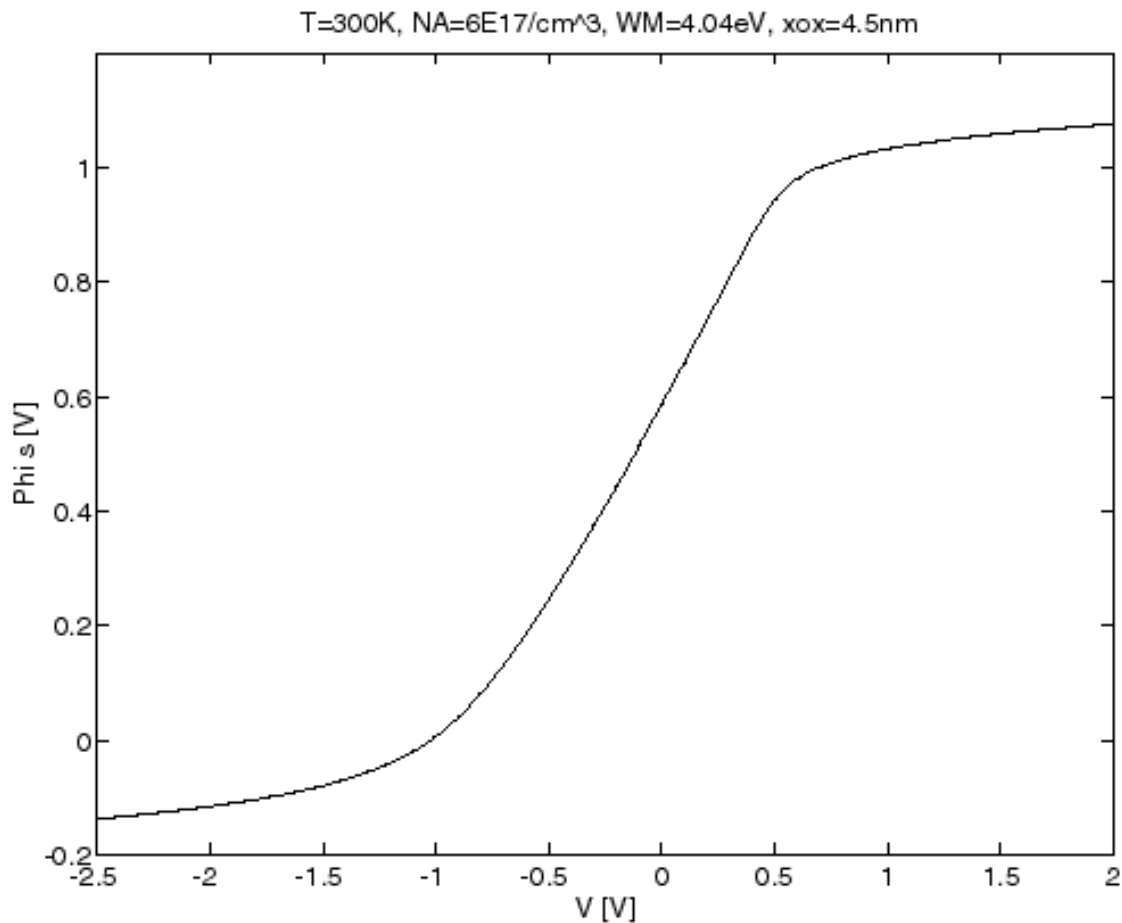
Key questions

- What are the key simplifications that one can make to the Poisson-Boltzmann formulation in order to develop simple first-order models for the various regimes of operation of the MOS structure?
- How thick are the inversion and accumulations layers?

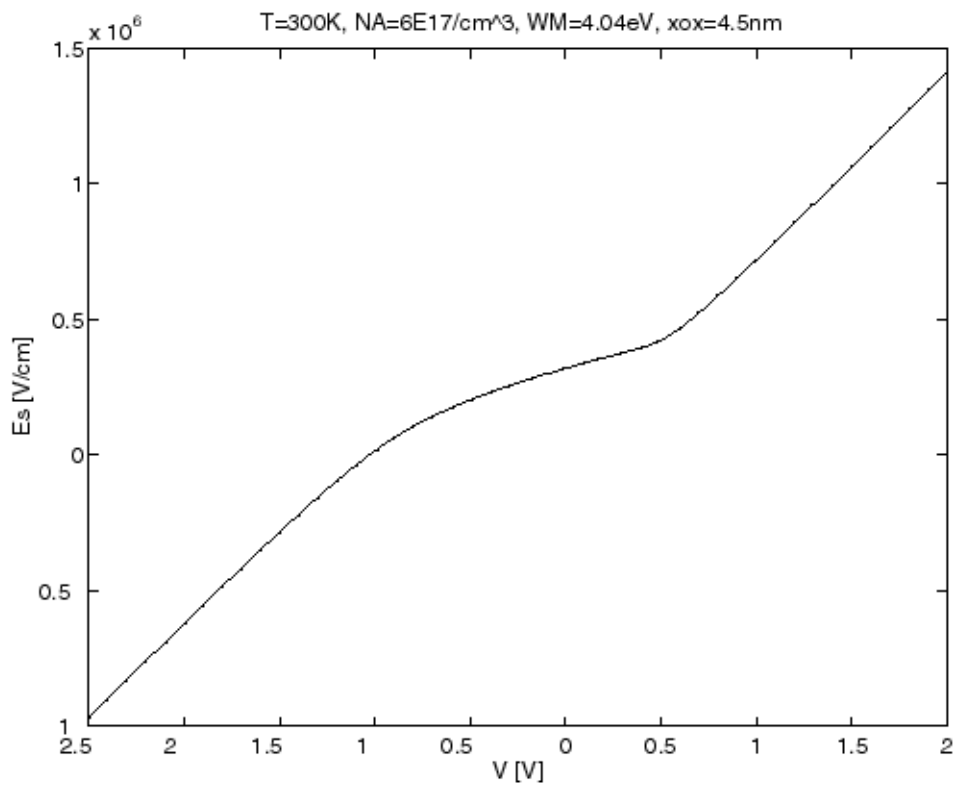
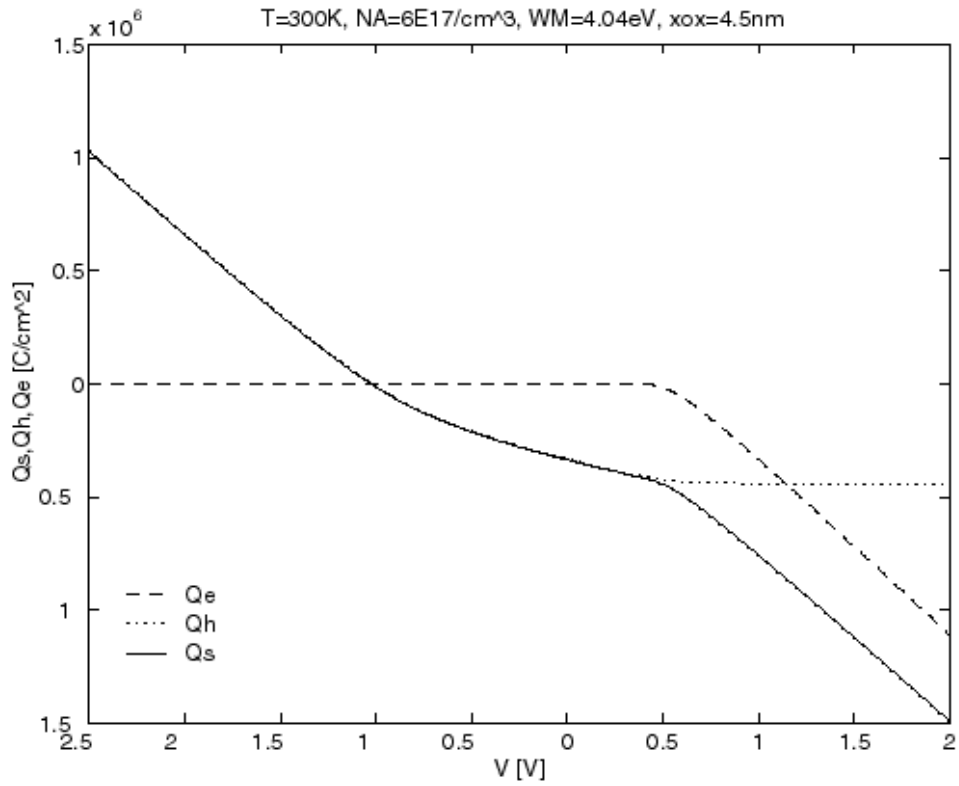
1. Ideal MOS structure outside equilibrium (*cont.*)

□ Next few viewgraphs: results of calculations for:

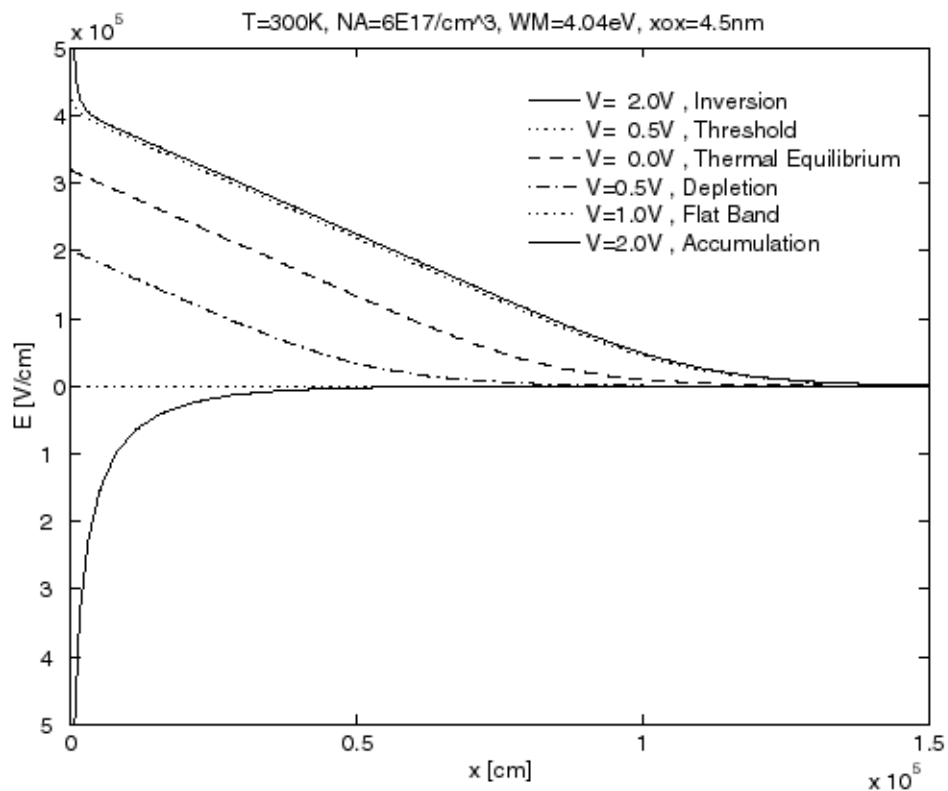
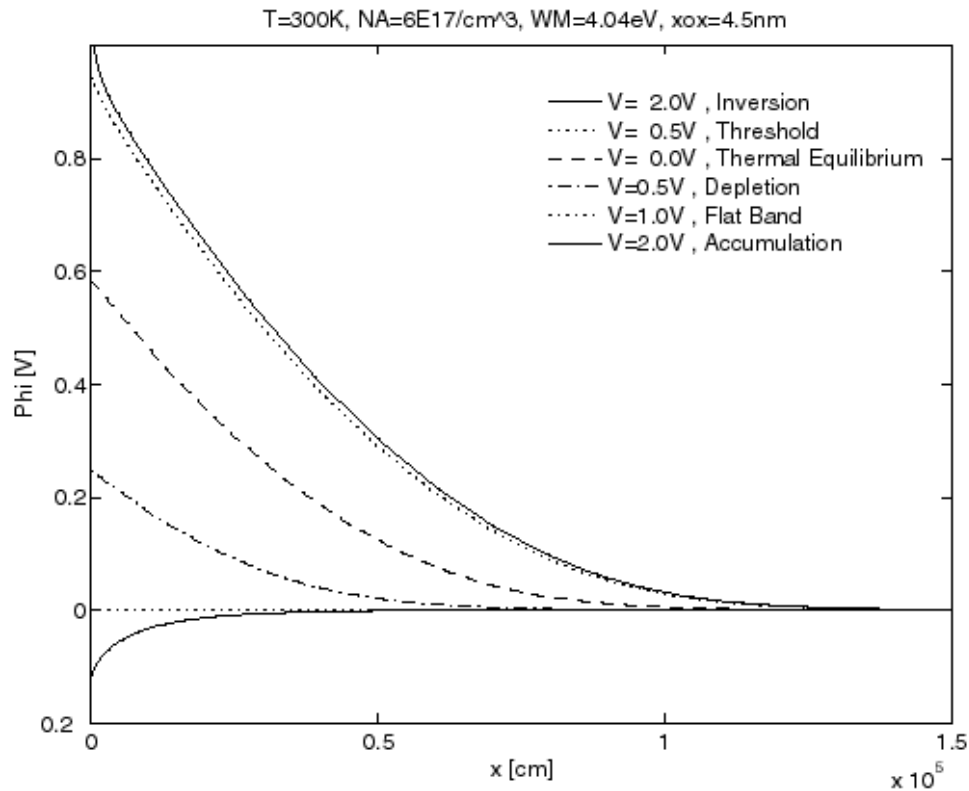
- $W_M = 4.04 \text{ eV}$ (n^+ polySi gate)
- $x_{ox} = 4.5 \text{ nm}$
- $N_A = 6 \times 10^{17} \text{ cm}^{-3}$
- $T = 300 \text{ K}$



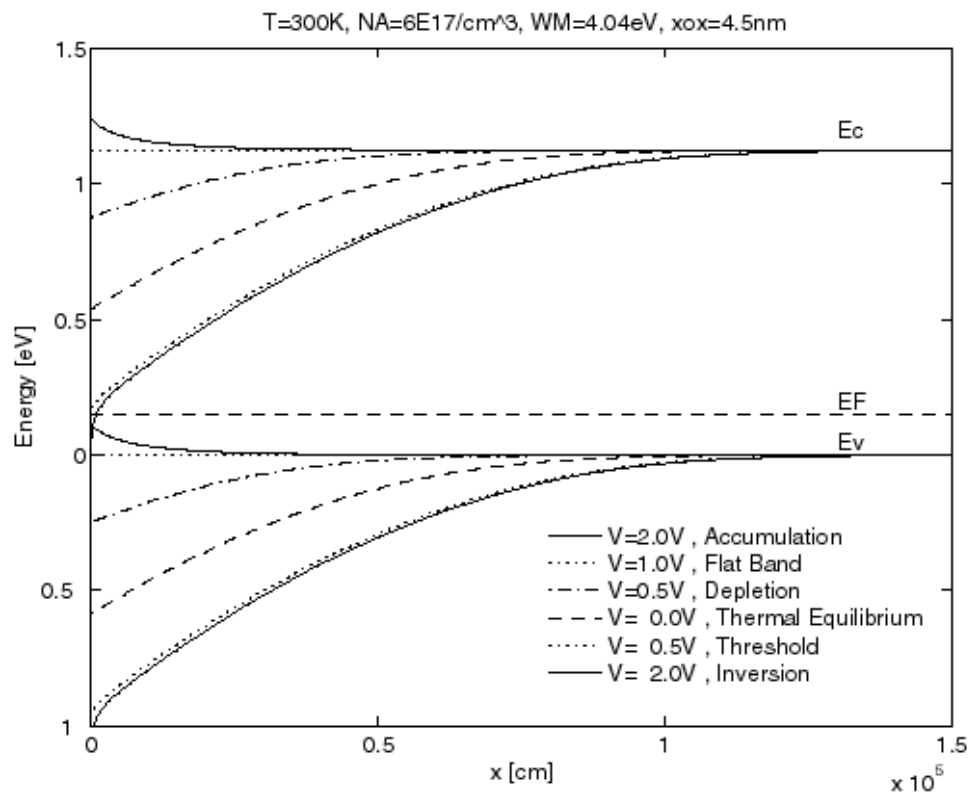
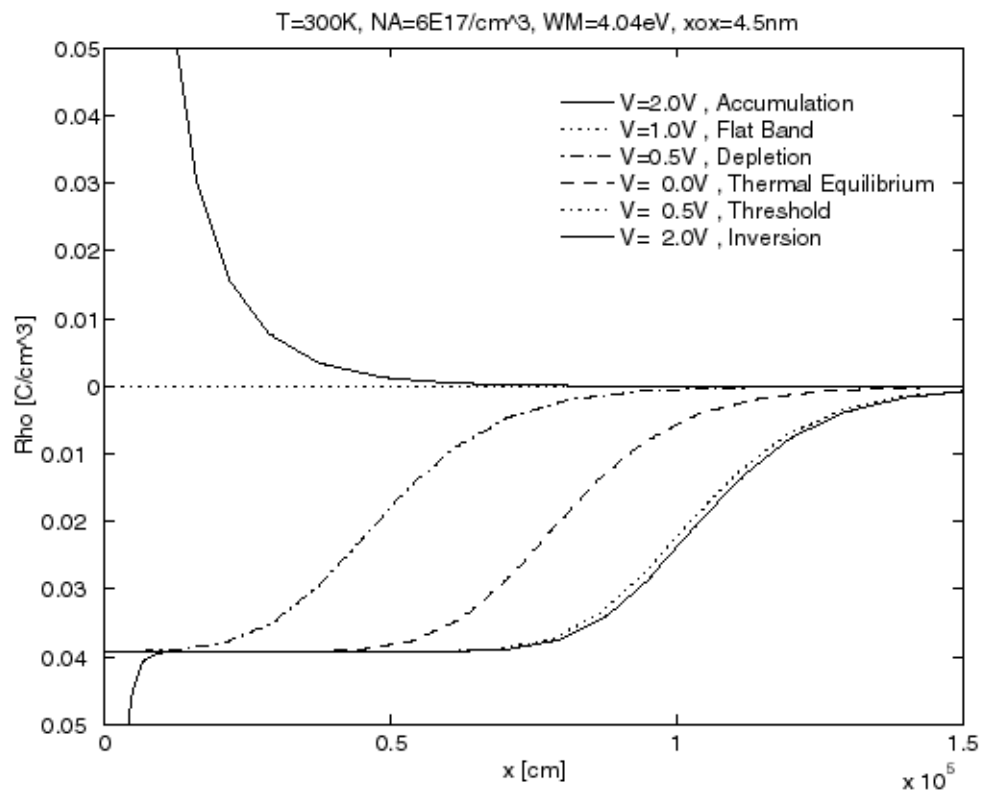
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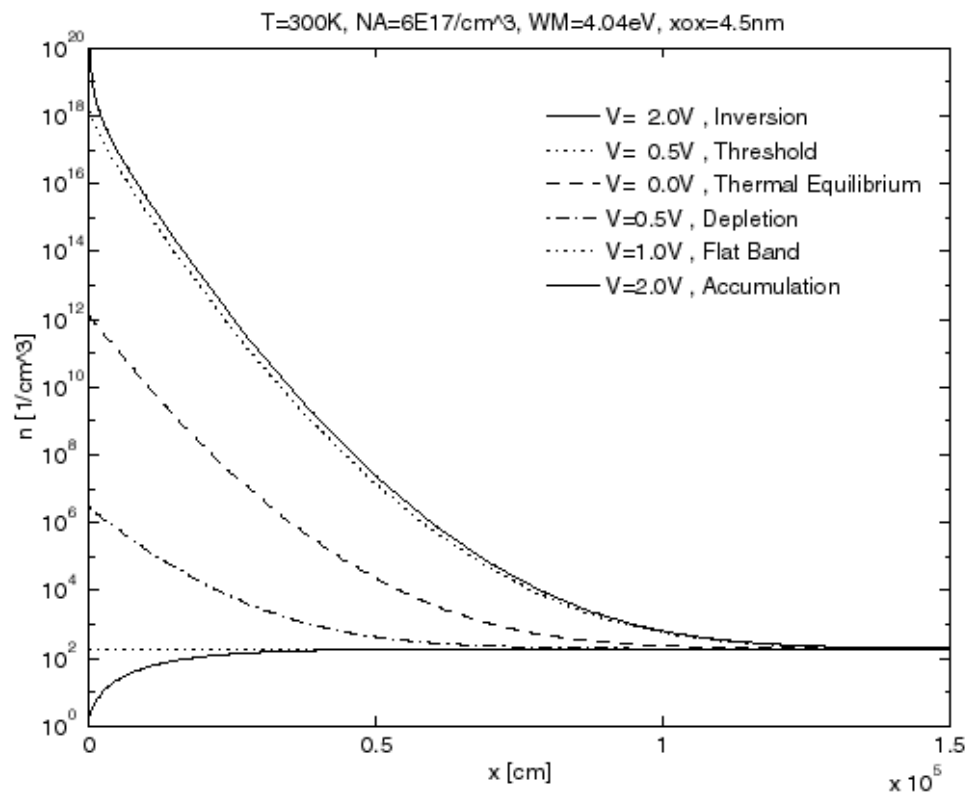
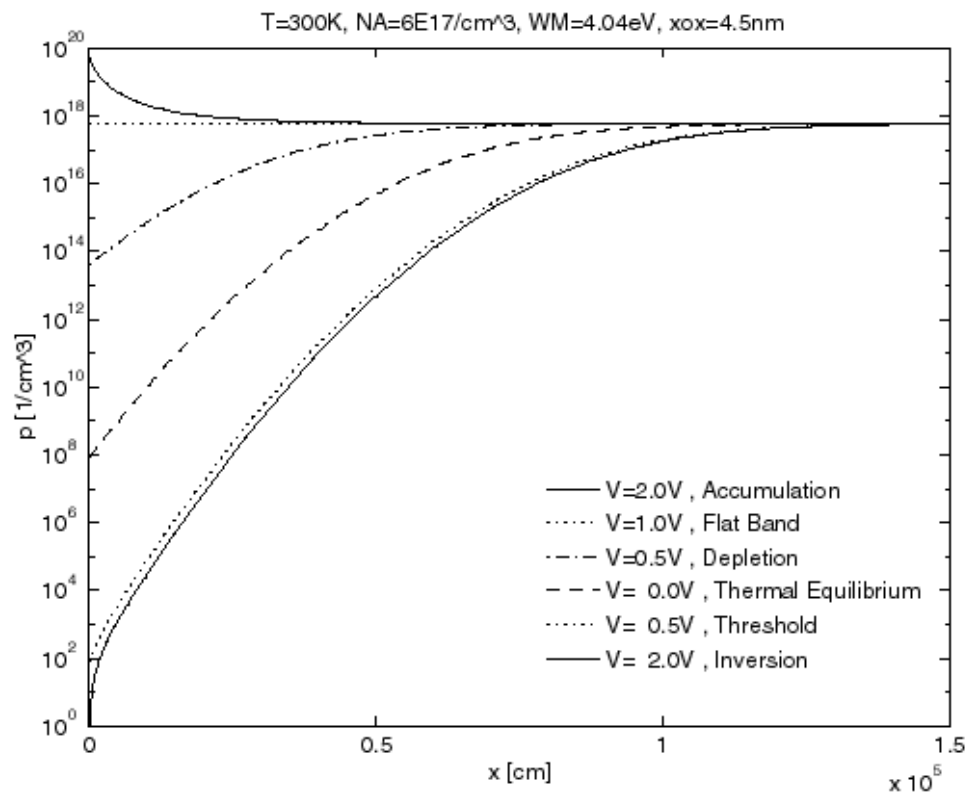
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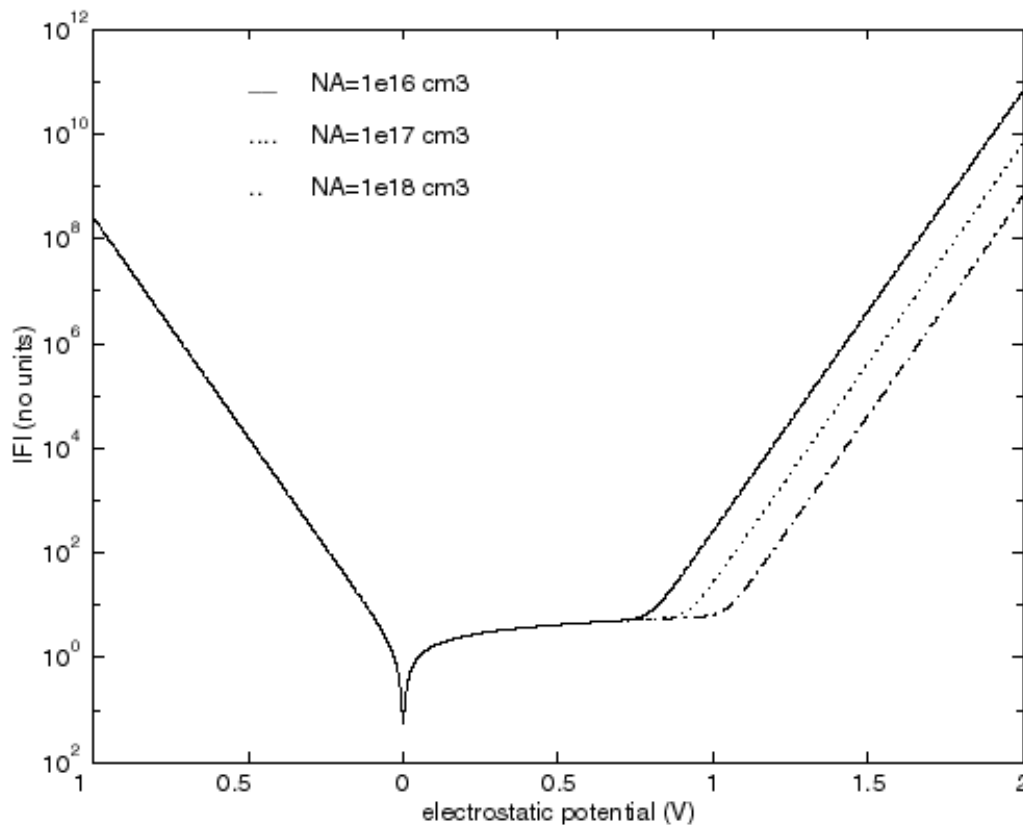
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□ Properties of $F(\phi)$ function:

$$F(\phi) = \frac{\phi}{|\phi|} \left[\left(\exp \frac{-q\phi}{kT} + \frac{q\phi}{kT} - 1 \right) + \frac{n_i^2}{N_A^2} \left(\exp \frac{q\phi}{kT} - \frac{q\phi}{kT} - 1 \right) \right]^{1/2}$$



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- For $\phi = 0$, $F(0) = 0$.
- For $\phi = 0$, $\frac{d^2F}{d\phi^2}|_0 = 0$.
- For $\phi < 0$, $F(\phi) < 0$. For $\phi > 0$, $F(\phi) > 0$.
- For all ϕ , $\frac{dF}{d\phi} > 0$.

- Last three terms multiplied by small prefactor:

$$\frac{n_i^2}{N_A^2} \sim 10^{-10} - 10^{-14}$$

- For $\phi < 0$ and $|\phi|$ more than a few $\frac{kT}{q}$:

$$F(\phi) \simeq -\exp\left(\frac{-q\phi}{2kT}\right)$$

- For $\phi > 0$ and ϕ more than a few $\frac{kT}{q}$, but not too large:

$$F(\phi) \simeq \sqrt{\frac{q\phi}{kT}}$$

- For $\phi > 0$ and sufficiently large:

$$F(\phi) \simeq \frac{n_i}{N_A} \exp\left(\frac{q\phi}{2kT}\right)$$

□ Approximations for **depletion**

$$F(\phi) \simeq \sqrt{\frac{q\phi}{kT}}$$

Yields:

$$x_d = \sqrt{\frac{2\epsilon_s\phi_s}{qN_A}}$$

Relationship between ϕ and V :

$$\phi_s = \frac{\gamma^2}{4} \left[\sqrt{1 + 4 \frac{V - V_{FB}}{\gamma^2}} - 1 \right]^2$$

Depletion charge:

$$Q_s = -\frac{1}{2} \gamma^2 C_{ox} \left[\sqrt{1 + 4 \frac{V - V_{FB}}{\gamma^2}} - 1 \right]$$

□ Approximations for **Accumulation**

$$F(\phi) \simeq -\exp\left(\frac{-q\phi}{2kT}\right)$$

Results in accumulation region thickness:

$$x_{acc} \simeq \sqrt{2}L_D$$

Relationship between V and ϕ_s :

$$\phi_s \simeq -\frac{2kT}{q} \ln\left[\sqrt{\frac{q}{kT}} \frac{1}{\gamma} (V_{FB} - V)\right]$$

Accumulation charge:

$$Q_h = Q_s \simeq \sqrt{2\epsilon_s kT N_A} \exp\left(\frac{-q\phi_s}{2kT}\right)$$

In terms of V :

$$Q_h \simeq C_{ox}(V_{FB} - V)$$

□ Approximations for **Inversion**

Piecewise description of $F(\phi)$:

$$F(\phi) \simeq \sqrt{\frac{q\phi}{kT}} \quad \text{for } \phi < 2\phi_f$$

$$F(\phi) \simeq \sqrt{\frac{q2\phi_f}{kT} + \exp\left(\frac{q(\phi - 2\phi_f)}{kT}\right) - 1} \quad \text{for } \phi > 2\phi_f$$

Results in inversion region thickness:

$$x_{inv} \simeq \sqrt{2}L_D$$

Depletion region thickness:

$$x_d = x_{inv} + \sqrt{\frac{2\epsilon_s 2\phi_f}{qN_A}} \simeq x_{dmax}$$

Relationship between ϕ_s and V :

$$\phi_s \simeq 2\phi_f + \frac{kT}{q} \ln\left[\frac{q}{kT} \frac{1}{\gamma^2} (V - V_{FB} - 2\phi_f)^2 - \frac{q2\phi_f}{kT} + 1\right]$$

Electron charge in inversion layer:

$$Q_e \simeq -\sqrt{2\epsilon_s kT N_A} \left[\sqrt{\frac{q2\phi_f}{kT} + \exp\left(\frac{q(\phi_s - 2\phi_f)}{kT}\right) - 1} - \sqrt{\frac{q2\phi_f}{kT}} \right]$$

In terms of V :

$$Q_e \simeq -C_{ox}(V - V_{th})$$

with:

$$V_{th} = V_{FB} + 2\phi_f + \gamma\sqrt{2\phi_f}$$

Assumed threshold surface potential $\phi_{sth} = 2\phi_f$. Empirically, often:

$$\phi_{sth} \simeq 2\phi_f + m\frac{kT}{q}$$

with m around 5.

Key conclusions

- Charge control relationship for inversion charge:

$$Q_e \simeq -C_{ox}(V - V_{th})$$

- Charge control relationship for accumulation charge:

$$Q_h \simeq C_{ox}(V_{FB} - V)$$

- Inversion and accumulation layer thickness of order of Debye length.
- Better choice for surface potential at threshold:

$$\phi_{sth} \simeq 2\phi_f + m\frac{kT}{q}$$

with m around 5.

Self study

- Derivation of analytical approximations for electrostatics in depletion, accumulation and inversion from Poisson-Boltzmann formulation.